



# **SiGe BiCMOS Technologies with RF and Photonic Modules**

Multi Project Wafer and  
Low Volume Production

# About Us

IHP GmbH is a German R&D institution, focused on wireless and broadband communication.

Core competencies are:

- Mixed signal process technology
- RF & digital circuit design
- Communication Systems Design

IHP is running an 8" pilot line housed in a 1.500 square meter class-3 cleanroom.

Several 0.25  $\mu\text{m}$  and 0.13  $\mu\text{m}$  SiGe BiCMOS technologies are available.

IHP Solutions GmbH is a 100% subsidiary of IHP. IHP Solutions was founded to focus on and grow the transfer of research results (technology transfer) of IHP research activities as well as the commercial partner for value added services along the value chain of IC manufacturing. In the context of IHP's service offerings IHP Solution is responsible for commercial IC production.



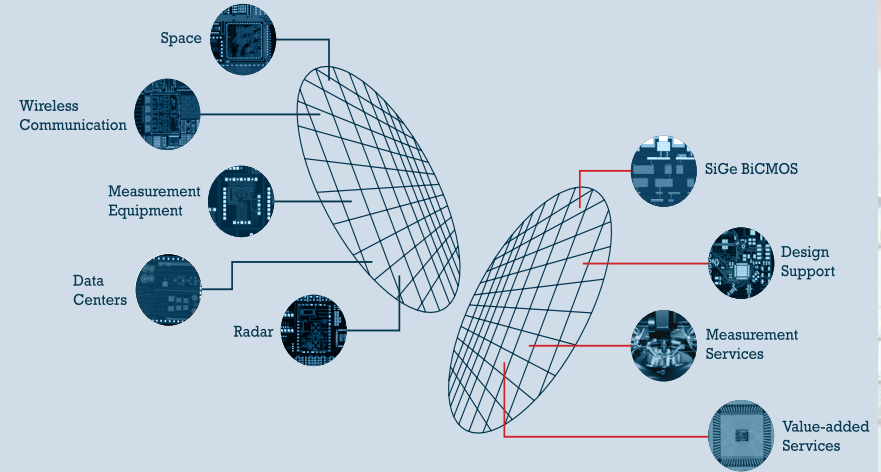
# Low Volume Production & MPW Service

IHP offers research partners and customers access to its powerful SiGe BiCMOS technologies and special integrated RF modules.

These technologies are especially suited for applications in the higher GHz bands (e.g. for wireless, broadband, radar).

They provide integrated HBTs with cut-off frequencies of up to 650 GHz.

- For products in fiber optics, aerospace, broadband and wireless communication, radar, data centers, measurement equipment, THz imaging, e-health
- SiGe BiCMOS with leading edge 650 GHz HBTs
- 8 inch wafer fab for research and production in Germany
- Reliable service since 2001



## SiGe BiCMOS Technologies for MPW & Prototyping

SG13S	A high-performance 0.13 $\mu\text{m}$ BiCMOS with npn-HBTs up to $f_T/f_{\text{max}} = 250/340$ GHz, with 3.3 V I/O CMOS and 1.2 V logic CMOS
SG13G2	A 0.13 $\mu\text{m}$ BiCMOS technology with higher bipolar performance of $f_T/f_{\text{max}} = 300/500$ GHz
SG25H5_EPIC	A monolithic photonic BiCMOS technology combining 0.25 $\mu\text{m}$ CMOS, high-performance npn HBTs ( $f_T/f_{\text{max}} = 220/290$ GHz), and full photonic device set for C/O-band
SG13G3Cu	A 0.13 $\mu\text{m}$ BiCMOS technology with higher bipolar performance of $f_T/f_{\text{max}} = 470/650$ GHz

## Standard AI-BEOL

The 0.13  $\mu\text{m}$  process offers five thin and two thick metal layers (TM1:2  $\mu\text{m}$  TM: 3  $\mu\text{m}$ )

Cu-BEOL model is available

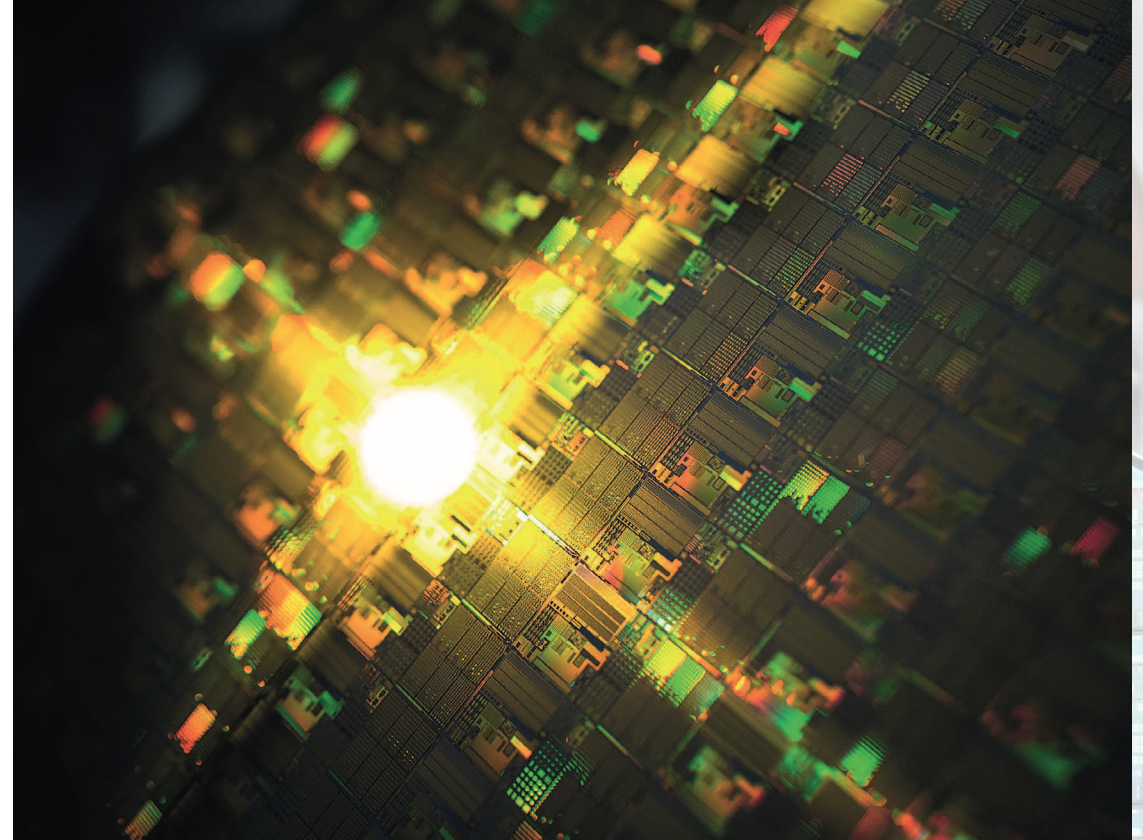
Cadence-based mixed signal Design Kits are available. For high frequency designs an analog Design Kit in ADS can be used. IHP's reusable blocks and IPs for wireless and broadband are offered to support your designs.

The shedule for MPW & Prototyping runs here:



# The Following Modules are Available

PIC	Additional photonic design layers together with BiCMOS BEOL layers on SOI wafers
LBE	The Localized Backside Etching module is offered to remove silicon locally to improve passive performance (available in all technologies)
TSV	Module is an additional option in SG13S and SG13G2 technology which offers RF grounding by vias through silicon to improve RF performance
MEMRES	A fully CMOS integrated memristive module based on resistive TiN/HfO <sub>2-x</sub> /TiN switching devices in SG13S technology. Process Design Kit including layout and VerilogA simulation model is also available.
TSV+RDL	Module is an additional option in SG13S and SG13G2 technology offers TSV with single redistribution layer on BiCMOS



# Key Specification

Feature	SG13S	SG13G2	SG13G3Cu	SG25H5_EPIC
Technology node (nm)	130	130	130	250
f <sub>max</sub> NPN (GHz)	340	500	650	290
CMOS core supply (V)	1.2, 3.3	1.2, 3.3	1.2, 3.3	2.5
C <sub>MIM</sub> (fF/μm <sup>2</sup> )	1.5	1.5	1.5	1.0
Poly Res (Ω/□)	250	275	275	305
High Poly Res (Ω/□)	1300	1360	1360	1600
BEOL	7× Al	7× Al	Cu	5× Al
Varactor (C <sub>max</sub> /C <sub>min</sub> )	1.7	1.7	1.7	3.3
Q inductor	37*	37*	37*	23.5

\*1 nH (with LBE)

# Bipolar Transistors

Feature	SG13S	SG13G2	SG13G3Cu	SG25H5_EPIC
NPN1 f <sub>T</sub> / f <sub>max</sub> (GHz)	250 / 340	300 / 500	470 / 650	200 / 280
NPN2 f <sub>T</sub> / f <sub>max</sub> (GHz)	45 / 165		260 / 600	
NPN3 f <sub>T</sub> / f <sub>max</sub> (GHz)			140/500	
NPN1 BV <sub>CE0</sub> (V)	1.7	1.7	1.4	1.7
NPN2 BV <sub>CE0</sub> (V)	3.7	2.5	1.8	
NPN3 BV <sub>CE0</sub> (V)			2.3	
NPN1 BV <sub>CBO</sub> (V)	5	4.8	3.7	5
NPN2 BV <sub>CBO</sub> (V)	15	8.5	5.5	
NPN3 BV <sub>CBO</sub> (V)			7.5	

## CMOS Section

Feature		SG25H5_EPIC	SG13S*	
Core Supply Voltage (V)		2.5	3.3	1.2
nMOS	$V_{TH}$ (V)	0.6	0.71	0.50
	$I_{OUT}$ ( $\mu A/\mu m$ )	540**	280	480
	$I_{OFF}$ (pA/ $\mu m$ )	3	10	500
pMOS	$V_{TH}$ (V)	-0.6	-0.61	-0.47
	$I_{OUT}$ ( $\mu A/\mu m$ )	-230	-220	-200
	$I_{OFF}$ (pA/ $\mu m$ )	-3	-10	-500

\* Parameters for SG13G2 and SG13G3Cu are similar

\*\* @ VG = 2.5 V

## Passive Section (AL-BEOL)

Feature	SG25H5_EPIC	SG13S	SG13G2	SG13G3Cu
MIM Capacitor (fF/ $\mu m^2$ )	1	1.5	1.5	1.5
P+ Poly Resistor ( $\Omega/\square$ )	360	250	260	260
High Poly Resistor ( $\Omega/\square$ )	1600	1300	1360	1360
Varactor $C_{max}/C_{min}$	3.3	1.7	1.7	1.7
Inductor Q@ 5 GHz	18 (1 nH)	18 (1 nH)	18 (1 nH)	18 (1 nH)
Inductor Q@10 GHz	20 (1 nH)	20 (1 nH)	20 (1 nH)	20 (1 nH)
Inductor Q @ 5 GHz	37 (1 nH)*	37 (1 nH)*	37 (1 nH)	37 (1 nH)

\* with LBE

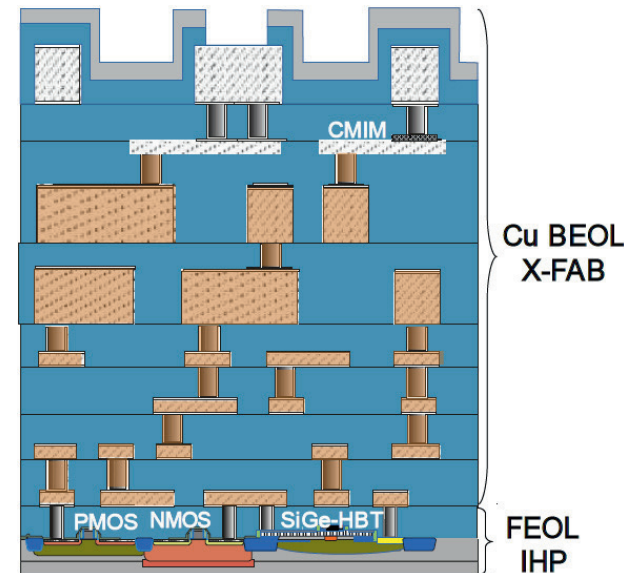
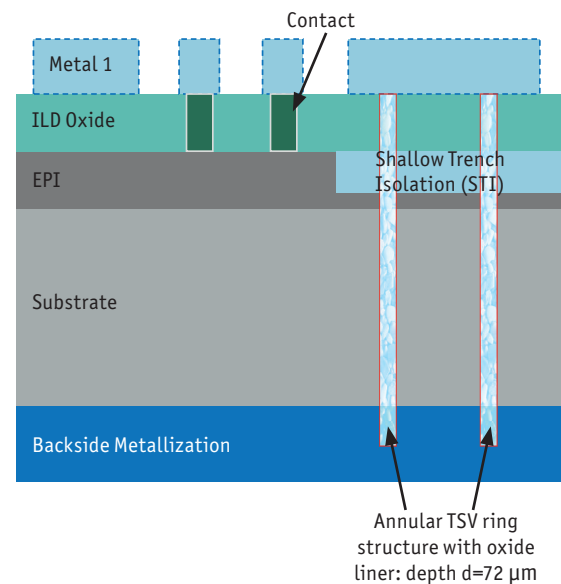


# TSV-Module and backside RDL

Through-Silicon Via Module for RF grounding available in SG13 technology.

Single TSVs can provide low GND inductance  $\approx 30$  pH to improve RF circuit performance.

A backside metallization is provided as chip-to-package interface for die attach.



SG13G/G2 FEOL



+

xfab

XR013 Cu BEOL

Joint foundry offer  
via IHP Solutions

- More than 2 times higher current handling of thin metal lines
- More than 3 times higher current handling of small vias
- 40% higher area density of MIM capacitor



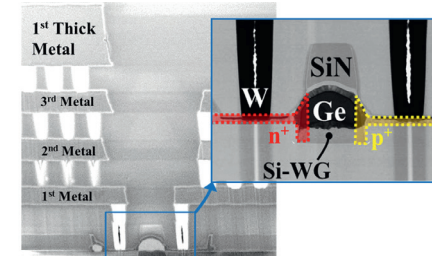
# Photonic Integrated Circuit Module

## Main features

- 220 nm Si on 2  $\mu\text{m}$   $\text{SiO}_2$
- 3 etching depths
- 4 doping levels (p, n, p+, n+)
- 3 + 2 thick Al backend metal layers
- Germanium photo diodes ( $f_{3\text{dB}} > 60$  GHz)
- HBTs ( $f_T/f_{\text{max}} = 220/290$  GHz)
- Optional localized backside etching
- Complements BiCMOS in SG25H5\_EPIC

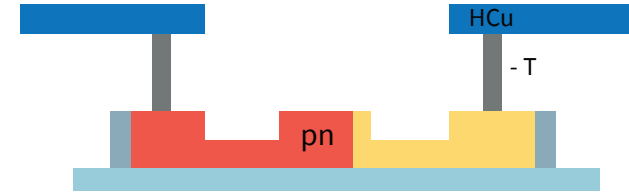
	Wave guides		
	Deep etch	Shallow etch	Medium etch
<b>Loss</b>	3.5 dB/cm	1.2 dB/cm	2.5 dB/cm
<b>Core width</b>	450 nm	700 nm	500 nm
<b>Features</b>		Grating etch	p, n, p+, n+possible

## Photo diode



- $I_{\text{dark}} < 200$  nA @ (-2 V, 20°C)
- IPKISS3 building block
- GDSII cell
- Responsivity:  $R_{\text{int}}(1550 \text{ nm}) \geq 0.7$  A/W  
 $(1310 \text{ nm}) \geq 0.8$  A/W
- Ge PD -3 dB Bandwidth > 60 GHz (-2 V)

## Phase shifter



## Typical values

- customized length
- $V_{\pi} = 4.3$  V,  $V_{\text{bias}} = -2.2$  V (for 7 mm length)
- $C = 1.8$  pF

# Design Kit

The design kits support a Cadence mixed signal platform.

Analog/Mixed-Signal Flow:

- Verification
  - Cadence and PVS DRC/LVS/QRC
  - Calibre DRC/LVS
- Selected PDKs offer Cadence Voltus FI
- EMX stack for SG13 technology with Al-BEOL and Cu-BEOL
- Empire support for all design kits
- ADS support via Golden Gate/RFIC dynamic link to Cadence available
- Sonnet support for all design kits

Digital Design Flow:

- Digital CMOS libraries and IO cells for 0.13 μm CMOS and 0.25 μm CMOS are available: Behavioral Models (Verilog), Timing Files (LIB) and Abstracts (LEF)
- Simulation: ModelSim (Mentor Graphics), Incisive Enterprise Simulator – IES (Cadence)
- Formal Verification: Formality (Synopsys)
- Scan Insertion and Test Pattern Generation: DFT Compiler/TetraMax (Synopsys)
- Place & Route: Encounter Digital Implementation System (Cadence)
- OA views of digital libraries are available for mixed-signal flow
- Power Analysis: PrimeTime with PrimePower Option (Synopsys)
- Static Timing Analysis: PrimeTime (Synopsys)

Models	SG25H5 EPIC	SG13S	SG13G2	SG13G3
PSP	x	x	x	
MOSVAR		x	x	
HSIM		x	x	x*
VBIC/HICUM	x	x	x	

EM simulations	SG25H5 EPIC	SG13S	SG13G2	SG13G3
Keysight momentum		x	x	
Sonnet		x	x	
EMX		x	x	x

SG13G3: VBIC<sub>max</sub>

Design platforms	SG25H5 EPIC	SG13S	SG13G2	SG13G3
Cadence Virtuoso & Virtuoso XL	x	x	x	x
Cadence Spectre & Spectre RF	x	x	x	x
Cadence VPS & Voltus FI		x	x	
Keysight ADS	x	x	x	x
Mentor Calibre DRC/LVS		x	x	x
TexEDA RFIC Studio	x	x	x	
IPKISS3	x			



Leibniz Institute  
for high  
performance  
microelectronics



## IHP

Dr. René Scholz

Phone: +49 335 5625 647

Email: [scholz@ihp-microelectronics.com](mailto:scholz@ihp-microelectronics.com)

Website: [www.ihp-microelectronics.com](http://www.ihp-microelectronics.com)

## IHP Solutions

Mirtha Vera Valenzuela

Phone: +49 335 5625 800

Email: [mirtha.valenzuela@ihp-solutions.com](mailto:mirtha.valenzuela@ihp-solutions.com)

Website: [www.ihp-solutions.com](http://www.ihp-solutions.com)

## Our Representatives

**Europractice** Thomas Drischel [virtual-asic@iis.fraunhofer.de](mailto:virtual-asic@iis.fraunhofer.de)

**Italy** Claudio Marziali [info@alfamicroonde.it](mailto:info@alfamicroonde.it)

**China/Asia** Dr. Yaoming Sun [y.sun@hk-microsystem.com](mailto:y.sun@hk-microsystem.com)

**USA/Canada/South America** Volker Blaschke [volker.blaschke@siliconrfsynergy.com](mailto:volker.blaschke@siliconrfsynergy.com)

